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(43)2003-0079705
2003 10 10(21) 10-2003-0019290
(22) 2003 03 27

(30) JP-P-2002-00098859 2002 04 01

(JP)

(71) 가 가
1 - 1 - 2(72) 1 1 2 가 가
1 1 2 가 가

1 1 2 가 가

(74)

:

(54)

,
 ,
 ,
 0.6 IPS
 ,
 ,
 d₁ (nm)
 ,
 Z 가 X , X , Y
 , N_z = (nx₁ - nz₁) / (nx₁ - ny₁)
 Re₁ = (nx₁ - ny₁) × d₁ 200 350nm
 nx₁, ny₁, nz₁ N_z ≥ 0.4

1
2
3

* * *

1: 1a:

1b: 2:

3: 4: IPS

, PDP, CRC , , IPS

TN , , , TN , , , |
PS , , 가 , , , |

, IPS , ,

가 , , 가 .

(shift)
4-305602
(wide viewing ang

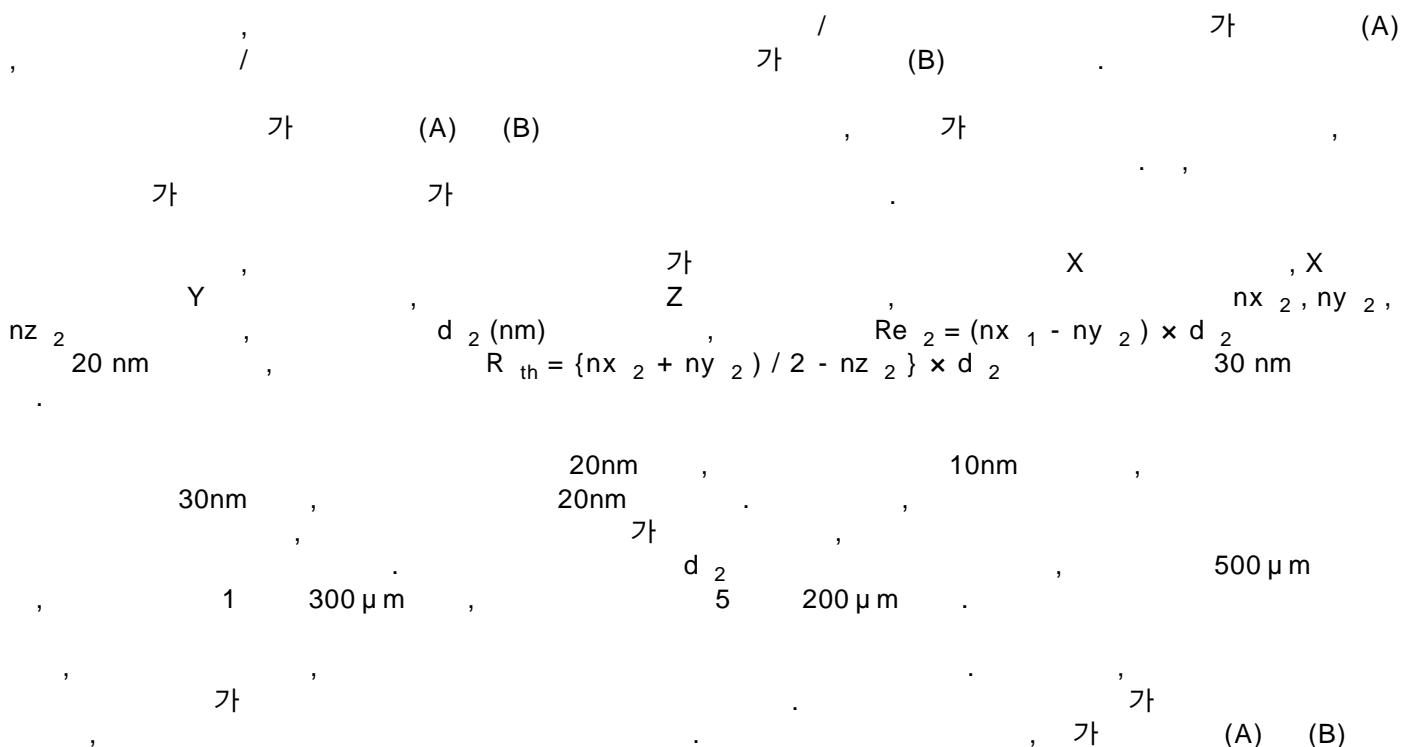
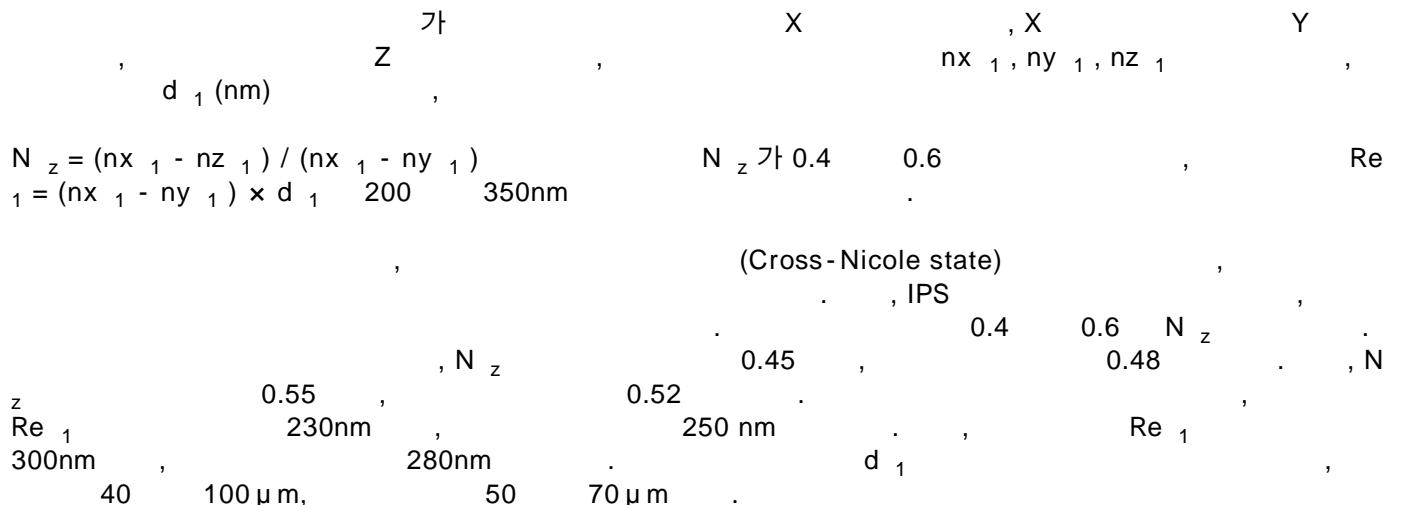
4-371903
le)

4-305602 , , ,
가 , , ,
가 .

4-371903 , , ,
) , , ,
TAC , , ,
TAC , , ,
가 , , ,
가 .
(TAC

IPS

(slow axis)



가

IPS

가

IPS

IPS

가

(A),

/

가

(B)

가
Z

X

, X
 nx_2, ny_2, nz_2

Y

 d_2 (nm)

$$R_{th} = \{nx_2 + ny_2\} / 2 - nz_2 \quad Re_2 = (nx_2 - ny_2) \times d_2 \quad 20 \text{ nm}$$

$$30 \text{ nm}$$

IPS

, IPS
IPS

가

, IPS

IPS

가

, 가 (A) (B)

(1)
(2)
(2)
(2)

(2)

1
(1b)
(1)
(2)

1
(1a)
(2)
(1)

(polyolefin);
nenaphthalate)

(polycarbonate);
(polyethylene terephthalate)
(polyesters);
(poly norbornene)

(polypropylenes)

(polyethylene
(cycloaliphatic)

phatic polyolefins); (polyvinyl alcohols); (polyvinyl butyrals);
 (polymethyl vinyl ethers); (polyhydroxyethyl acrylates);
 (hydroxyethyl celluloses); (hydroxypropyl celluloses); (methylcelluloses); (polyallylates); (polysulfones); (polyether sulfone s); (polyphenylene sulfides); (polyphenylene oxides); (poly allyl sulfones); (polyvinyl alcohols); (polyamides); (polyimides); (polyvinyl chlorides); (cellulose based polymers); (binary copolymers); (ternary copolymers); (graft copolymers); (blended materials) . , , , / (heat shrinking film)

(heat shrinking film) , /

(conjugated linear atomic group) (; mesogen)

, (discotic polymer), (cholesteric polymer)
 crylates), , (polysiloxanes), (polya
 ted cyclic compound unit) (polymethacrylates), (poly malonates), ,
 (para-substituted cyclic compound unit)

3 7

(soil) (blocking inhibitor)

가 (A) / 가 , 가
 . , 가 . . , . ,
 가 . . , . ,
 . (ester bonding) (amid bond)

(fumaronitrile)

, (vinyltoluene), (methoxy styrene), (chloro styrene) (styrene),

가 (B) , 가 (A) 가 (B) , AS , ABS , ASA

$$\text{가} \quad \begin{matrix} (\text{B}) \\ , 1 \times 10^{-4} \end{matrix} \quad \begin{matrix} 5 \times 10^{-5} \\ . \end{matrix} \quad , \quad \begin{matrix} 1 \times 10^{-3} \\ 5 \times 10^{-6} \end{matrix}$$

가 (A) 가 (B), 가 95% (B) 50%, 95% (A) 50%, 90% (B) 40%

(AS)

(sticking)

가

0.5 50 μm
25

()

IPS

UV

가

가

가

가

2 3
3)
 (4)
1))
 (1a)

3

(3)

(3)

(

2

(3) IPS

(4)

(1)

가

3
가

(4)

4

(3) IPS

(4)

(3)

1

()

, ()

$$\frac{1}{2}, \quad \left(\frac{1}{2} \right) \quad \left(\frac{1}{4} \right) \quad \left(\frac{1}{4} \right).$$

$$\begin{pmatrix} & & \\ & , 3 \\ (&) \end{pmatrix} \quad .$$

가

가

가

50 가

가

1
가

EF)

F350, Merck Co., Ltd.

Transmax ()

(NITTO DENKO CORPORATION

D - B

PC

550nm

(pale color light)

1/4

1/2

1/4

, が

2

, が

2

VA , , IPS

2

(Oji Scientific Instruments KOBRA21ADH

 n_x, n_y, n_z
 R_{e_1}
 R_{e_2}
 R_{th}

1

()

 $n-$
25 28 (n-
15 % 50 %) 75

100 10 , 140 10 , 160 30 , 100 μm
, , , , , Re₂ 4 nm

R

th

()

(; 20 μm)

()

, 65 μm , 260nm Re_1 , $N_z = 5$

()

2 , IPS

가

(가)

, 45
50
ntrast (ELDIM) 200 60 95% RH 70 EZ Co

2

1 160 1.5 160 MD 1.5 Re₂, 12nm TD
 R_{th} 45 μm , 4nm

1

45
40
70
200 60 95% RH

3

1

IPS

, 45
50
70 200 60 95% RH

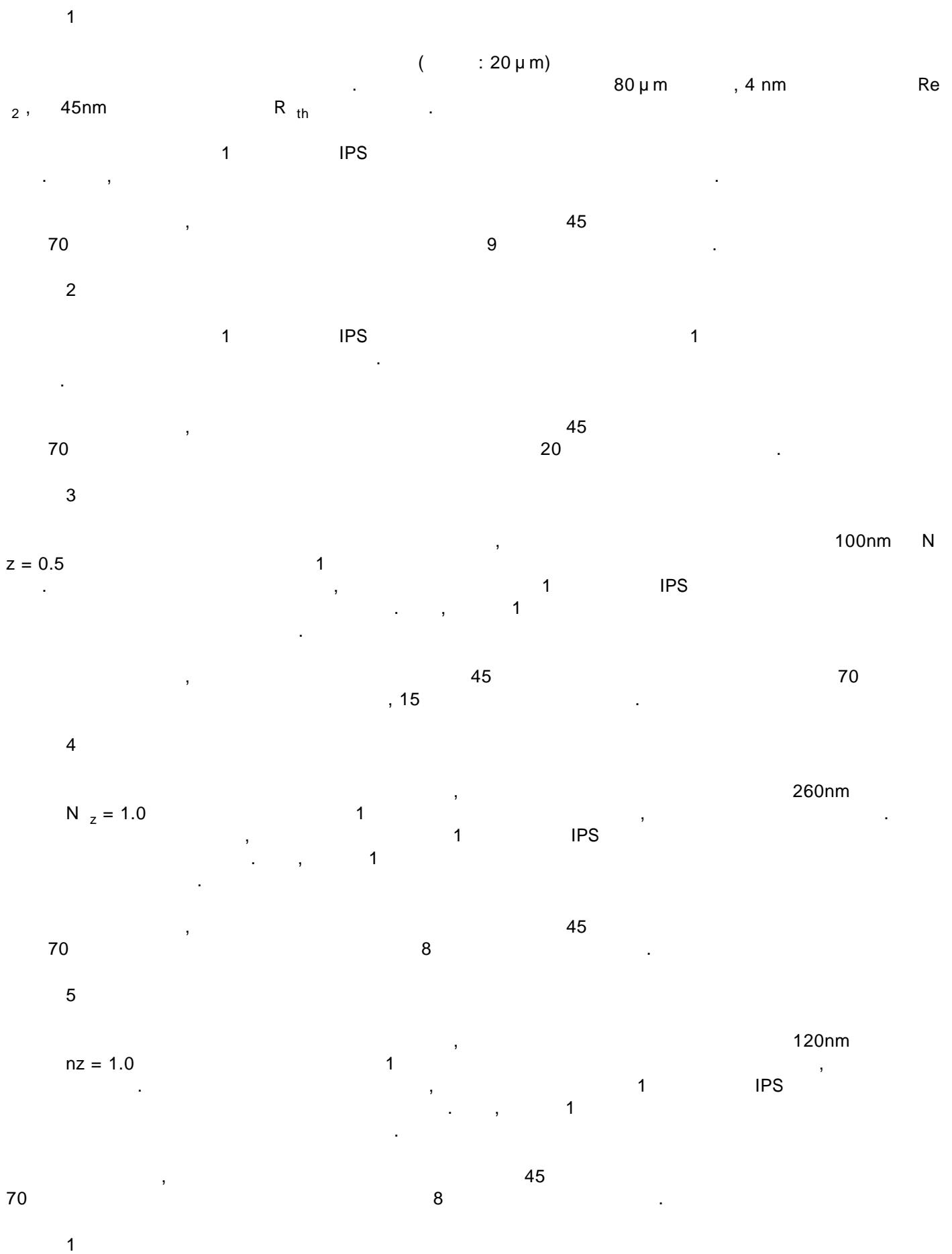
4

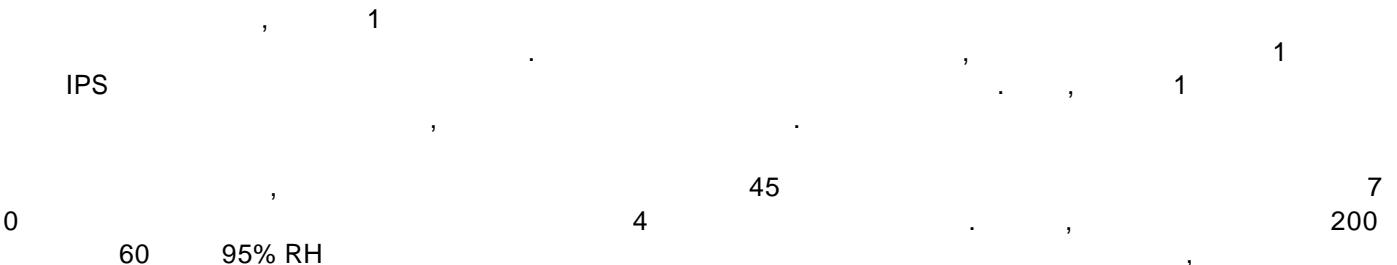
()

N-
/g , 147) 65 (N- 75 %, 28 %, 0.01
35 72 % T (T dice type extruder) 160 MD 1.7 Re₂, 160 135 μm TD 1.
8 55 μm , 1nm 3nm R_{th}
 R_{th}

1

70 , 55 45
60 95%RH 200



(: 20 μm)

(57)

1.

,

가 n_x , n_y , n_z
 d_1 (nm) x

$$N_z = (n_x - n_z) / (n_x - n_y) \quad N_z \approx 0.4 \quad 0.6$$

$$d_1 = (n_x - n_y) \times d_1 \quad 200 \quad 350\text{nm} \quad Re$$

2.

1 ,

,

3.

2 ,

,

(side chain) / 가 (A);
/ 가 (B)

4.

2 ,

가 n_x , n_y , n_z
 d_2 (nm) x

$$\{ \times d_2 \quad Re_2 = (nx_2 - ny_2) \times d_2 \quad 20 \text{ nm} \quad , \quad R_{th} = \{(nx_2 + ny_2) / 2 - nz_2\}$$

$$30 \text{ nm}$$

5.

3 ,

6.

1 ,

7.

, 1 ,

,

가

IPS

8.

7 ,

,

/

가 (A);

/

가 (B)

IPS

9.

7 ,

d₂ (nm)가
Z

,

X

, X
nx₂, ny₂, nz₂

Y

,

$$\{ \times d_2 \quad Re_2 = (nx_2 - ny_2) \times d_2 \quad 20 \text{ nm} \quad , \quad R_{th} = \{(nx_2 + ny_2) / 2 - nz_2\}$$

$$30 \text{ nm}$$

10.

8 ,

IPS

11.

,

1

,

가

IPS

12.

11 ,

,

/ 가 (A);

/ 가 (B) IPS

13.

11

가
Z

X

, X
 nx_2, ny_2, nz_2

Y

, d_2 (nm)

$$\{ \times d_2 = (nx_2 - ny_2) \times d_2 \quad 20 \text{ nm} \quad \text{IPS}$$

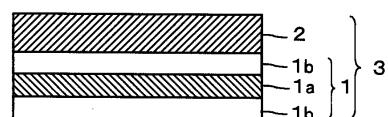
$$R_{th} = \{nx_2 + ny_2\} / 2 - nz_2$$

14.

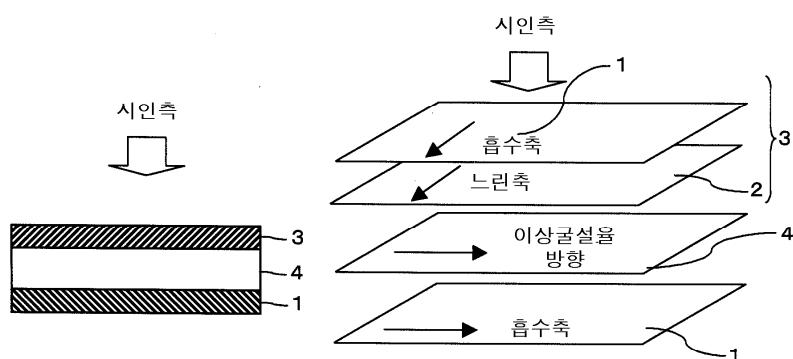
12

IPS

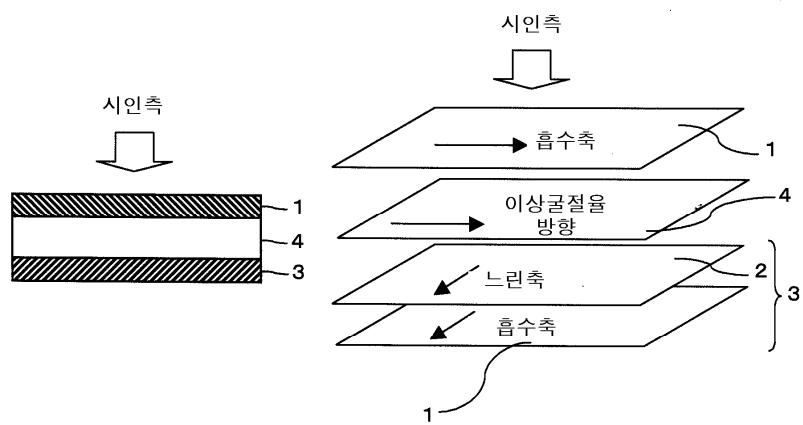
1



2



3



专利名称(译)	光学薄膜和图像显示系统		
公开(公告)号	KR1020030079705A	公开(公告)日	2003-10-10
申请号	KR1020030019290	申请日	2003-03-27
[标]申请(专利权)人(译)	日东电工株式会社		
申请(专利权)人(译)	日东电工 (株) 制		
当前申请(专利权)人(译)	日东电工 (株) 制		
[标]发明人	YANO SHUUJI 야노슈우지 NISHIDA AKIHIRO 니시다아끼히로 MAEDA HIROE 마에다히로에		
发明人	야노슈우지 니시다아끼히로 마에다히로에		
IPC分类号	G02F1/1343 G02F1/13363 G02B5/30		
CPC分类号	G02F1/133634 G02F1/134363		
代理人(译)	韩国专利公司		
优先权	2002098859 2002-04-01 JP		
外部链接	Espacenet		

摘要(译)

垂直于X轴方向的方向被定义为相位差膜的X轴，其成为相应膜平面侧内的折射率，是偏振片的吸收轴和相位的慢轴的最大值。差异膜是垂直度，或者平行的光学膜定义为Y轴。膜的厚度方向定义为Z轴。并且相应的 n_x 1 和称为面内相位差 $\Delta\phi = (n_x - n_y) \cdot d$ 的光学膜的值为200到350nm。 N_z 表示为 $N_z = (n_x - n_y) / (n_x + n_y)$ 满足其定义为 $0.4 < N_z < 0.6$ 的范围，并且 d 和薄膜的厚度定义为 $d = 1 \text{ nm}$ 可以实现容易显示它所看到的轴向折射率当应用于用于液晶显示器的图像显示系统时，在宽范围内，优选地用于以面内切换模式操作。相位差板，偏振片和光学膜。

